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(22) 1998 10 08 (43) 1999 05 25

(30) 08/946,980 1997 10 08 (US)
(73) 600 (: 07974 - 0636)
(72) 334
11
1

(74)

:

(54)

IC (interconnection pattern) IC (upper
IC chip) (via) (solder bump)
- - (chip - on - chip package) (layout) ,
가 (air isolated crossover) .

1 - - ,
 2 - - ,
 3 - - ,
 4 - - 2 ,
 5 3 4 ,
 6 5 ,
 7 , ,
 8 , " (wrong way)" ,
 9 가 .

62, 87, 88, 91, 92, 106, 114, 115 :

63, 64, 65, 72, 73, 74, 93, 94, 95, 96, 97, 98, 101, 105, 116, 118,

121, 123 :

67 : 68, 69, 104 :

71 : 75 :

81, 103, 111 : 82, 112, 113 :

83, 84, 85, 86 :

102 : 117, 119, 122 :

- - (chip - on - chip assembly)

(power module) (package design)
 ss memory) () (logic)
 , DRAM(dynamic random access memory) SRAM(static random acce
 , (device) (mem

가 (runner) (top) (air isolated crossover connection)

1 (12, 13) (11) 가 (Application Specific Integrated Circuit : ASIC) (footprint) 가

(12, 13) (11) 1 (14) (edge array) 가

(routing)

(flexibility) (11) (12, 13) 가 (11) 2 (31) (32) IC (polyimide) (capping) (thick insulting layer)(32) SINCAPS() (32) (32) 가 (photodefinable polymer) (33) IC (window) (32) (35, 36, 37) (35) (33) (32) 가 (36, 37) y- (38) (35) (39) IC (42) 가 (41) 가 (44) (under bump metallization)(45, 46)

(direct)

(in - board)

2

I/O

4

가

(51, 52, 53, 54)

1

(55, 56)

2

가

(55, 56)

(51, 53)

2 (level metal)

가 5

5 (interconnection arrangement)

(support chip)

(upper chip)

5

(contact pad) (62)

가

(61)

가

(runner) (63, 64, 65)

(solder bump)

(68, 69)

(67)

(61)

(flip chip bond)

(under bump metallization) (71)

(6

7) (72, 73, 74)

(73)

(68, 69)

(64)

(75)

(air isolated)

(interconnection assembly)

(air isolation)"

(filler material),

(thermal expansion effect)

(epoxy)

(passive gap)

5

(71)

(tin)

(fomulation)

가

(wetta

ble)

(conductivity)

(chrom

ium)

(copper)

(composite)

(organic)

(inorganic)

가

IC

, SiO

2, SINCAPS,

(polyimide)

(aluminum)

(solder alloy)

(thin layer of copper)

UBM

(interface integrity)

(sputtering)

(alloy target)

가

(graded composition) 가

가 1 , 500 - 5000 , 1000 - 3000
 (refractory) 가 , (dielectric layer) , (Ti - Pd - Au)
 . 2 Cr/Cu , (crossion resistant interface)
 , (transition layer) 가 ,
 , (co - spatter layer) , 1000 - 500
 0 , 2000 - 3000 .

, 1000 - 10000 가 , 2000 - 6000 가 가
 . (46) 가 가
 (eutectic) (melting point) , 가
 Cr/Cu (wet) . (gold layer)
 (oxidation) 500 - 3000 , 1000 - 2
 000 .

08/825,923 (1997 4 2) 가 , 가 .

5 가 6 , , 가 (64)
 (73) (74) (65) 6 .
 , x y , 45 ° ,

(81) " - " 7 (82) .
 (83, 84, 85, 86) (81) (87, 88)
 (82) (91, 92) . (93, 94, 95) (81) ,
 (96, 97, 98) (82) .
 , (96) (94) , (97) (95) .

(via) , ,
 , (footprint) 가
 - - 가 가
 , (thermal distribution) (heat sinking) .

d. 2 2 1 1 (space)

e. 2 — 2 — 2

2.

1 , 1 2 (runner) , 1 2

3.

1 , (solder bump)

4.

2 , 1 1 1 , 1 2 2 2 2 1 2 2

5.

4 , 1 1 가 1 3 2 , 2 가 , 1 2 , 2

6.

2 , 2 1 1 , 1 1 2 1 2 2 2 1 2 1

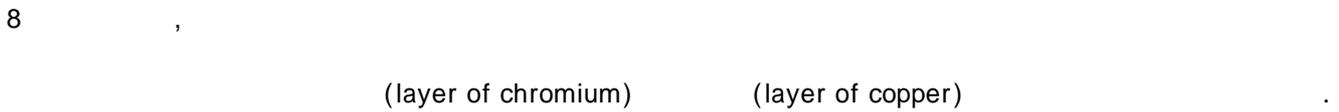
7.



8.



9.



10.

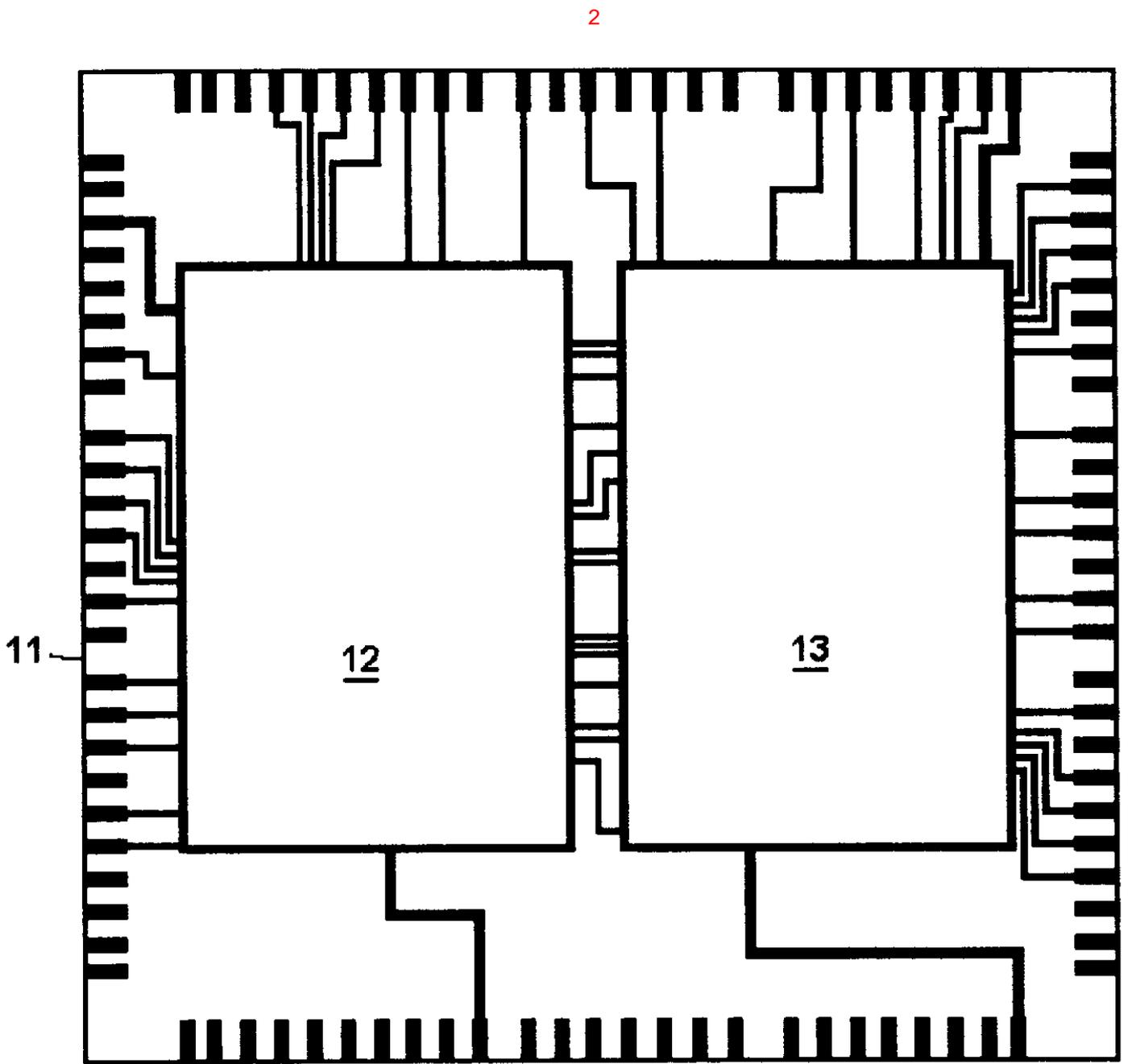
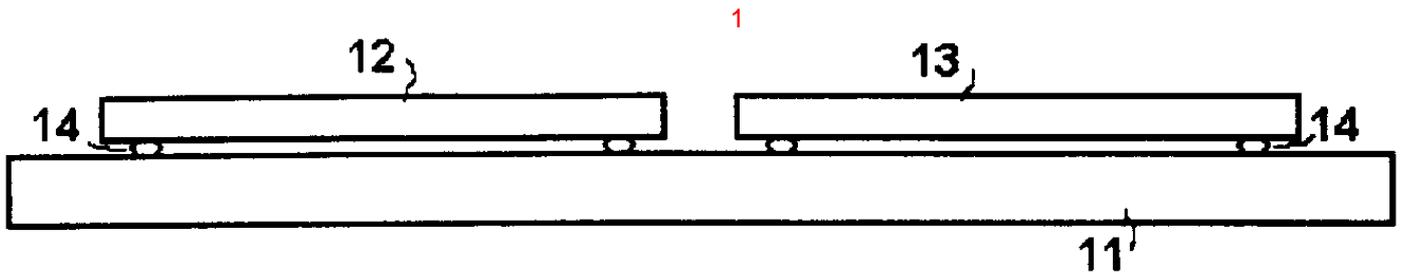


11.



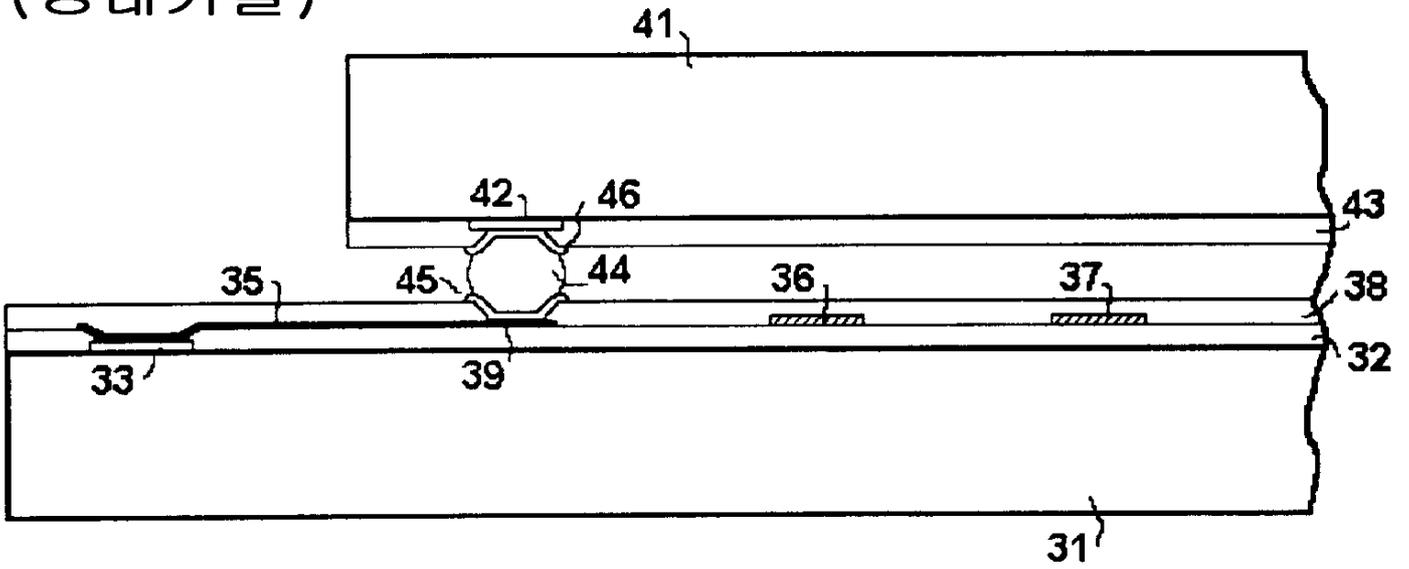
12.

- a. A_1 가 , L_1, W_1 , $L_1 \times W_1$, A_1 가
 - b. 1 1 ,
 - c. 1 2 , L_2, W_2 , A_2 가 , $A_2 (A_2 < A_1)$ 가
 - d. 1 3 , L_3, W_3 , A_3 가 , A_3 가 , L_3, W_3 , $A_3 < A_1$
- 1 , $A_2 + A_3 < A_1, L_2 + L_3 < L_1$, $W_2 + W_3 < W_1$,



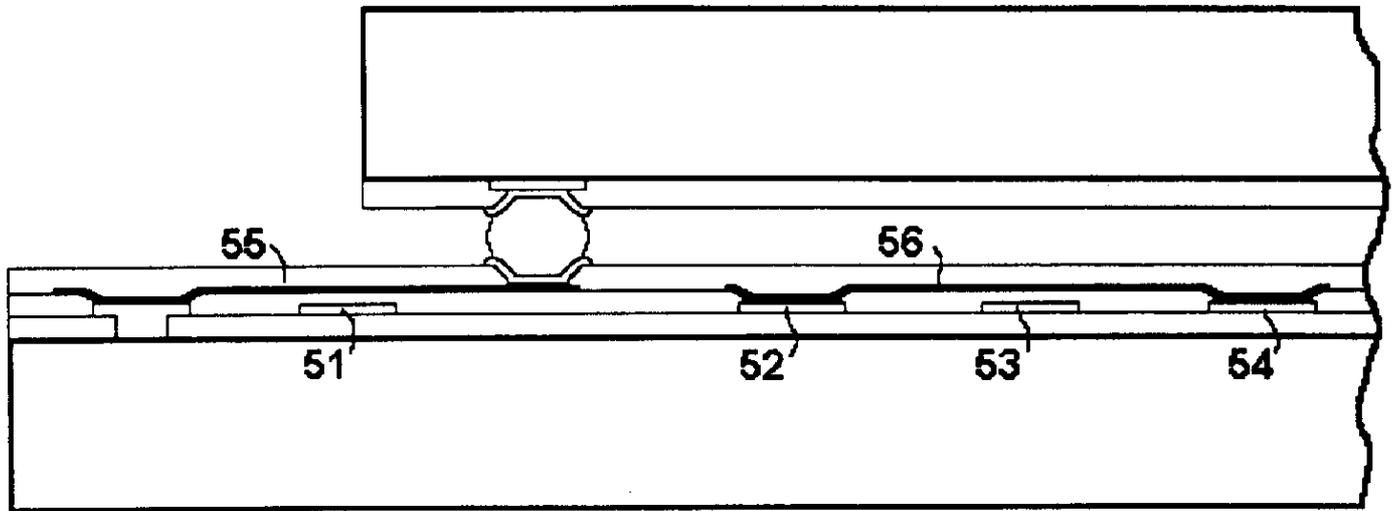
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(종래기술)

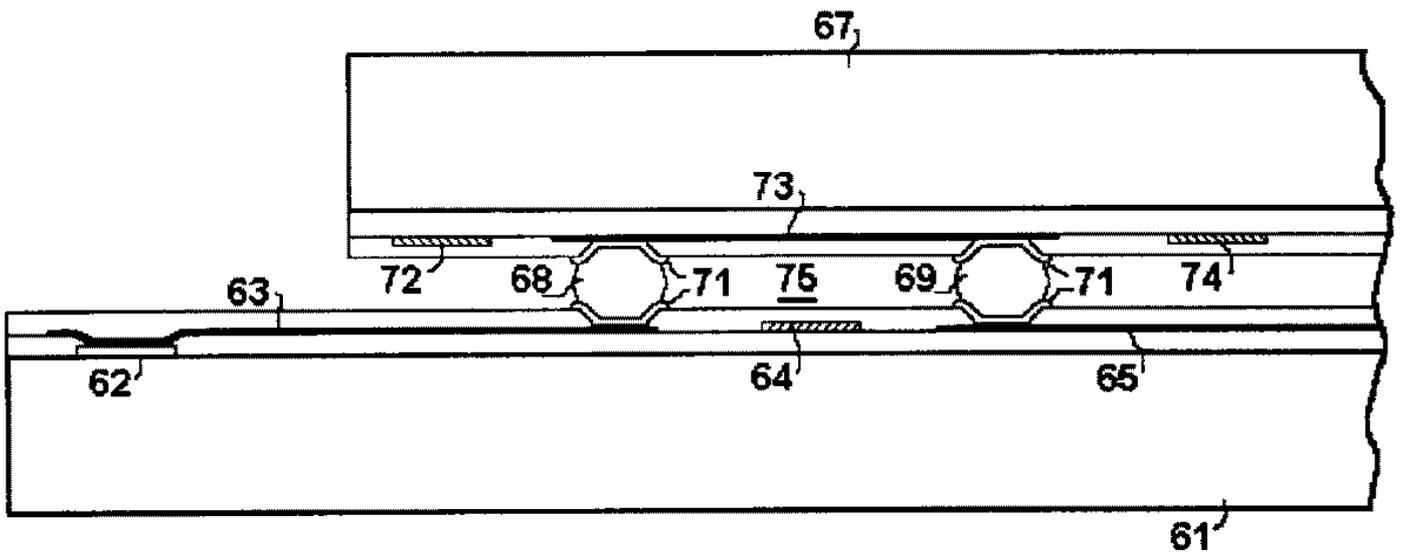


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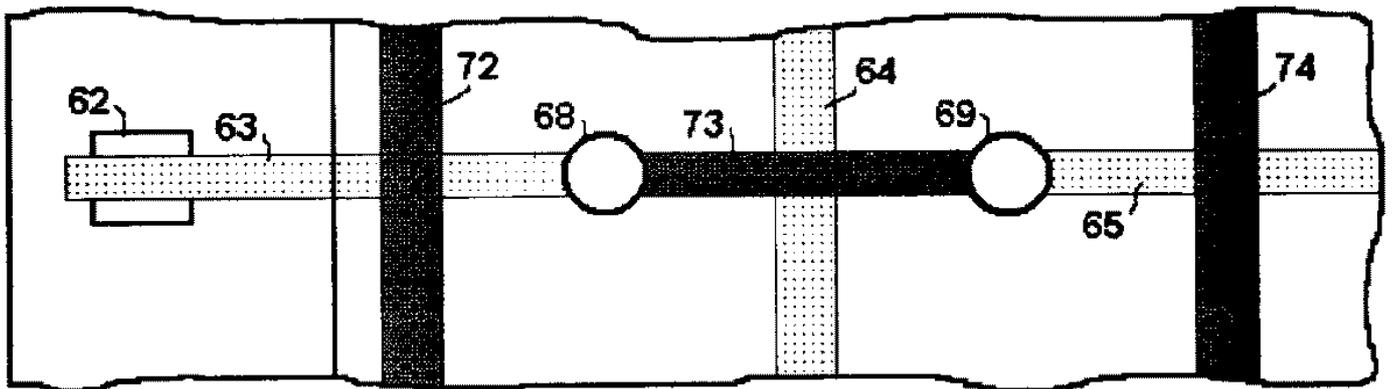
(종래기술)



5



6



7

